

L Number	Hits	Search Text	DB	Time stamp
1	2	("20020086222").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 12:45
2	2	jp-04136854-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:07
3	419602	mask photomask photo-mask reticle	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:07
4	11816	krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:07
5	322491	photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:08
6	421918	photoresist photo-resist resist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:08
7	4696	MOMOSE-SATOSHI-.in. MOMOSE-SATOKO-.in. MOMOSE-S-.in. ARAI-TADASHI-.in. ARAI-TADASHI-PROF-DR-.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:08
8	146	ARAKI-TSUTOMU-.in. yamaguchi-osamu-.in. (MOMOSE-SATOSHI-.in. MOMOSE-SATOKO-.in. MOMOSE-S-.in. ARAI-TADASHI-.in. ARAI-TADASHI-PROF-DR-.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:08
9	7	ARAKI-TSUTOMU-.in. yamaguchi-osamu-.in.) and (mask photomask photo-mask reticle) (MOMOSE-SATOSHI-.in. MOMOSE-SATOKO-.in. MOMOSE-S-.in. ARAI-TADASHI-.in. ARAI-TADASHI-PROF-DR-.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:12
10	2621548	ARAKI-TSUTOMU-.in. yamaguchi-osamu-.in.) and (mask photomask photo-mask reticle) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) transmit\$7 transmission	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:11
11	5	(MOMOSE-SATOSHI-.in. MOMOSE-SATOKO-.in. MOMOSE-S-.in. ARAI-TADASHI-.in. ARAI-TADASHI-PROF-DR-.in. ARAKI-TSUTOMU-.in. yamaguchi-osamu-.in.) and (mask photomask photo-mask reticle) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:15
12	614196	shade shield\$3 opaque	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:18
13	1332	(mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 (shade shield\$3 opaque))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:22

14	4	((mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 (shade shield\$3 opaque))) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:25
15	233480	attenuat\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:20
16	59	(mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 attenuat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:23
17	1	((mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 attenuat\$5)) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:24
18	19	((mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 (shade shield\$3 opaque))) ((mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 attenuat\$5))) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:28
19	31	(mask photomask photo-mask reticle) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) with (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:35
20	77786	3.ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:35
21	6397	430/5.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:35
22	79647	3.ti. 430/5.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:36
23	1	(3.ti. 430/5.ccls.) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) with (blank (quartz adj substrate)) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:49

24	3338	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) with (blank (quartz adj substrate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:36
26	8	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) with (blank (quartz adj substrate))) same ((krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission)) (blank (quartz adj substrate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:43
27	243122		USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:49
28	32	(photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:51
29	9	(3.ti. 430/5.ccls.) and ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:52
30	15163	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 polymer\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:55
31	0	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 polymer\$5 with ((blank (quartz adj substrate))) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 13:59
32	0	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 polymer\$5) same ((blank (quartz adj substrate))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:00
33	2	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 polymer\$5) with (mask photomask photo-mask reticle) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:00
34	4	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 polymer\$5) same (mask photomask photo-mask reticle) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:22

35	411	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:22
36	94	(3.ti. 430/5.ccls.) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:28
37	722932	"%"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:28
38	781142	percent percentage	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:28
39	1224949	"%" (percent percentage)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:29
40	10929	(transmit\$7 transmission) near2 ("%" (percent percentage))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:30
41	19	((transmit\$7 transmission) near2 ("%" (percent percentage))) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:30
42	807	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:36
43	71511	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:37
44	101	((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("%" (percent percentage))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:44

45	9	(3.ti. 430/5.ccls.) and ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:43
46	92	((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage))) not ((3.ti. 430/5.ccls.) and ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:44
47	86	((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:44

48	81	(((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("%") not ((3.ti. 430/5.ccls.) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:45
49	110	(((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:45
50	105	(((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ((transmit\$7 transmission))) not ((3.ti. 430/5.ccls.) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 14:58

51	321	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:01
52	9	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 attenuat\$5 near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:06
53	19	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) same (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:04
54	62	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:24
55	186	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:36
56	48	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:12
57	8	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:15

58	102	(((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:15
59	94	(((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission))) not (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:16

60	57	<pre> ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission))) not (((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) and ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)))) and (3.ti. 430/5.ccls.) </pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:16
61	45	<pre> ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and ((krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) SAME (transmit\$7 transmission)) </pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:25
62	503	<pre> ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5 (shade shield\$3 opaque)) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) </pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 16:13
63	792	<pre> (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission) </pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:39

64	0	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5 (shade shield\$3 opaque)) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) same ((krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:39
65	28	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5 (shade shield\$3 opaque)) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and ((krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 15:56
68	3	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5 (shade shield\$3 opaque)) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) same ((krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 16:14
69	194	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate)))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 16:14
70	29	((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and ((krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/04 16:14